

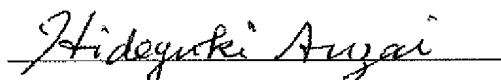
DECLARATION

I, Hideyuki ANZAI of Nerima-ku, Tokyo, Japan hereby declare that I have knowledge of the Japanese and English languages and that the writing contained in the following pages is believed to be a correct translation of the Japanese Patent Application No. 2003-197799 entitled:

METHOD FOR FORMING TRANSPARENT CONDUCTIVE FILM

Declared in Tokyo, Japan

On this 1st day of May, 2009


Hideyuki ANZAI

[NAME OF DOCUMENT] SCOPE OF PATENT CLAIMS

[Claim 1] A method for forming a transparent conductive film comprising a first process and a second process,

the first process comprising the step of forming a film on the substrate by discharging a gas 1 containing a film forming gas under a first discharge condition, and

the second process comprising the step of exposing the substrate to a gas 2 containing an oxidizing gas.

[Claim 2] The method for forming a transparent conductive film of claim 1, wherein the first process and the second process are alternately repeated a plurality of times.

[Claim 3] The method for forming a transparent conductive film of claim 1 or 2, wherein the second process is carried out in a discharge space.

[Claim 4] The method for forming a transparent conductive film in any one of claims 1 to 3, wherein a thickness of the accumulated film in the first process per batch is not more than 10 nm.

[Claim 5] The method for forming a transparent conductive film in any one of claims 1 to 4, wherein a temperature of the second process is 120°C or more and the oxidizing gas is oxygen.

[Claim 6] The method for forming a transparent conductive film in any one of claims 1 to 4, wherein a temperature of

the second process is 80°C or more and the oxidizing gas is ozone.

[Claim 7] The method for forming a transparent conductive film in any one of claims 1 to 6, wherein in the first discharge condition, the discharge gas is nitrogen, and a high frequency electric field is applied by superposing two high frequency electric fields having different frequencies between electrodes which are facing each other.